

FIG. 1.

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UVTech Systems Inc., PhotoChemical Ablation Model									
Case Definition		Gas Parameters			Material Parameters			Chemical	
Removed Material	AZ 2400 Photo Resist	Reactive Gases	Starting Partial Pressure (Torr)	Partial Pressure Increment (Torr)	Molecular Cross Section (x 10 ⁻²⁰ cm ²)	Material Absorption Coefficient (micron ⁻¹)		Photo-chemical parameter 1	0.002
	Reactive Gases	Gas 1 (Ozone)	1	0	67.50	Material Threshold (mJ/cm ²)		Photo-chemical parameter 2	0.02
Laser Wavelength (nm)	Ozone+ Oxygen		1	0	810.00				
			1	0	762.75				
			1	0	0.07				
			1	0	0.00675				
		Gas 2 (Oxygen)	499	0	0.0000675	Material Refractive Index			
			499	0	0	2.10			
			499	0	0	1.90			
			499	0	0	1.86			
		other	499	0	0	1.74			
			0	0	0				
			0	0	0				
			0	0	0				
Pulse Fluence	Base Fluence Value (mJ/cm ²)	Total Pressure	500			Angle of Incidence (Degrees)		Spectral Dependencies	
	Fluence Increment (mJ/cm ²)	Optical Path Through Gas (cm)	500						
50	1	3	500			Reflectivity Amplitude (s & p)		Absorption Properties (Arbitrary Units)	
	30		500			Reflectivity Component (s & p)			
52			500			Total Reflectivity		Wavelength (nm)	
			500						
		60			62				

FIG. 2.

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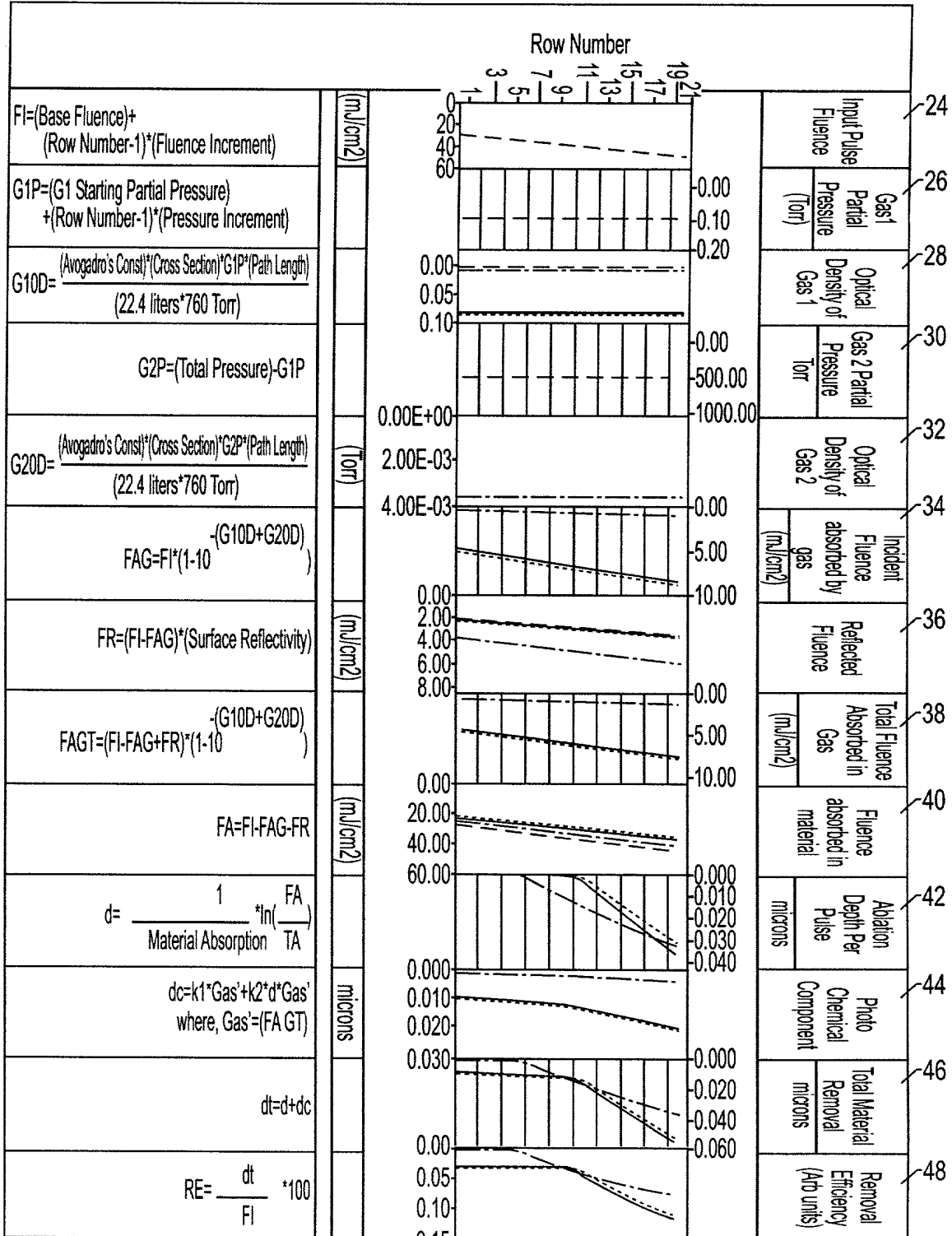


FIG. 3.

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FIG. 4.